## Amendments to the Claims:

The following listing of claims will replace all prior versions, and listings, of claims in the application:

(Currently Amended) An electro-optical device comprising, above a substrate:
 <u>a</u> data <u>lines-line</u> extending in a first direction;

<u>a</u> scanning <u>lines-line</u> extending in a second direction and intersecting the data <u>lines; line;</u>

<u>a pixel electrodes electrode</u> and <u>a thin film transistors transistor</u> disposed so as to correspond to <u>an intersection regions region</u> of the data <u>lines line</u> and the scanning <u>lines;</u> line;

<u>a</u> storage <u>capacitors capacitor</u> electrically connected to the thin film <del>transistors</del> transistor and the pixel <u>electrodes</u>; electrode; and

<u>a</u> shielding <u>layers layer</u> disposed between the data <u>lines line</u> and the pixel <u>electrodes</u>, electrode,

a nitride films-film being included in the shielding layers layer and are being formed along the data lines-line and being wider than the data-lines. line.

- 2. (Currently Amended) The electro-optical device according to Claim 1, a planarization process being performed on the surfaces a surface of an interlayer insulating films film arranged as the bases a base of the pixel-electrodes. electrode.
- 3. (Currently Amended) The electro-optical device according to Claim 1, each of the data lines line being formed of the same film as one of a pair of electrodes which constitute each of the a storage-capacitors, capacitor.
- 4. (Currently Amended) The electro-optical device according to Claim 3, the data <u>lines-line</u> forming a laminated structure of an aluminum film and a conductive polysilicon film.

5. (Currently Amended) The electro-optical device according to Claim 1, further comprising:

<u>a</u> relay <u>layers layer</u> being electrically connected to the pixel <u>electrodes</u> <u>electrode</u> and one of a pair of electrodes which constitute <u>each of the a</u> storage <u>capacitors</u>.

- 6. (Currently Amended) The electro-optical device according to Claim 5, the relay <u>layers layer</u> being made of <u>an aluminum films film</u> and <u>a nitride films. film</u>.
- 7. (Currently Amended) The electro-optical device according to Claim 5, the shielding <u>layers layer</u> being formed of the same <u>films-film</u> as the relay <u>layers. layer.</u>
- 8. (Currently Amended) The electro-optical device according to Claim 1, the nitride films-film being formed on the surfaces a surface of the data-lines. line.
- 9. (Withdrawn-Currently Amended) An electro-optical device comprising, above a substrate:

a data lines line extending in a first direction;

<u>a</u> scanning <u>lines-line</u> extending in a second direction and intersecting the data <u>lines; line;</u>

<u>a pixel electrodes electrode</u> and <u>a thin film transistors transistor</u> disposed so as to correspond to <u>an intersection regions region</u> of the data <u>lines line</u> and the scanning lines;

<u>a</u> storage <u>eapacitors capacitor</u> electrically connected to the thin film <del>transistors</del> transistor and the pixel <u>electrodes</u>; electrode; and

<u>a</u> shielding <u>layers layer</u> disposed between the data <u>lines line</u> and the pixel <u>electrodes, electrode</u>,

a nitride films film being included in the data-lines.line.

- 10. (Withdrawn-Currently Amended) The electro-optical device according to Claim 9, the nitride films-film being formed in regions-a region where the scanning-lines extend. line extends.
- 11. (Withdrawn-Currently Amended) The electro-optical device according to Claim 9, the nitride films-film being formed around an image display regions-region defined as regions-a region where the pixel-electrodes, electrode, the data-lines, line and the scanning lines-line are formed.
- 12. (Withdrawn-Currently Amended) The electro-optical device according to Claim 9, the nitride films-film formed on the data lines line being wider than the data lines. line.
- 13. (Withdrawn-Currently Amended) The electro-optical device according to Claim 12, each of the edges edge of the nitride films-film being larger than each of the edges edge of the data lines line by 0.1 to 2.2 μm.
- 14. (Withdrawn-Currently Amended) The electro-optical device according to Claim 9, the thickness of the nitride films-film being 10 to 100 nm.
- 15. (Withdrawn-Currently Amended) The electro-optical device according to Claim 9, further comprising:

another substrate that faces the substrate with an electro-optical material interposed therebetween and <u>a light-shielding films-film</u> formed on the other substrate so as to correspond to the scanning <u>lines-line</u> and the data <u>lines</u>, <u>line</u>,

the nitride films film being narrower than the light-shielding films. film.

16. (Withdrawn-Currently Amended) The electro-optical device according to Claim 15, each of the edges edge of the nitride films-film being smaller than each of the edges edge of the light-shielding films-film by up to 1 μm.

17. (Withdrawn-Currently Amended) The electro-optical device according to Claim 9, further comprising:

another substrate that faces the substrate with an electro-optical material interposed therebetween and <u>a light-shielding films-film</u> formed on the other substrate so as to correspond to the scanning <u>lines line</u> and the data <u>lines, line</u>.

the nitride films film being wider than the light-shielding films. film.

- 18. (Currently Amended) The electro-optical device according to Claim 1, the shielding layers-layer being formed of a transparent conductive material and are being formed over the an entire surface of the substrate.
- 19. (Withdrawn-Currently Amended) The electro-optical device according to Claim 9, the shielding layers-layer being formed of a transparent conductive material and being formed over the entire surface of the substrate in a mat shape.
- 20. (Withdrawn-Currently Amended) An electro-optical device comprising, above a substrate:

a data lines-line extending in a first direction;

<u>a</u> scanning <u>lines line</u> extending in a second direction and intersecting the data <u>lines;</u> line;

<u>a pixel electrodes electrode</u> and <u>a thin film transistors transistor</u> disposed so as to correspond to <u>an intersection regions region</u> of the data <u>lines line</u> and the scanning <u>lines</u>; <u>line</u>;

<u>a</u> storage <u>eapacitors</u> <u>capacitor</u> electrically connected to the thin film <del>transistors</del> transistor and the pixel-electrodes; electrode; and

<u>a</u> shielding <u>layers layer</u> disposed between the data <u>lines line</u> and the pixel <u>electrodes</u>, <u>electrode</u>,

a dielectric films film which constitute constitutes the storage capacitors

capacitor being made of a plurality of layers including different materials and one of the

plurality of the layers being made of a material having a higher dielectric constant than those

of the other layers, and

a nitride films film being included in the data lines. line.

21. (Currently Amended) An electronic apparatus having an electro-optical device comprising, above a substrate:

a data lines-line extending in a first direction;

<u>a</u> scanning <u>lines-line</u> extending in a second direction and intersecting the data <u>lines;</u> line;

<u>a pixel electrodes electrode</u> and <u>a thin film transistors transistor</u> disposed so as to correspond to <u>an intersection regions region</u> of the data <u>lines line</u> and the scanning <u>lines</u>; <u>line, the thin film transistor including a semiconductor layer;</u>

<u>a</u> storage <u>capacitors capacitor</u> electrically connected to the thin film <del>transistors</del> transistor and the pixel <u>electrodes</u>; <u>electrodes</u>;

a relay layer electrically connected with the pixel electrode;

a first contact hole electrically connecting the semiconductor layer of the thin film transistor with the data line;

a second contact hole electrically connecting the semiconductor layer of the thin film transistor with the relay layer; and

<u>a</u> shielding <u>layers</u> disposed between the data <u>lines</u> and the pixel <u>electrodes</u>, <u>electrode</u>,

a nitride films film being included in the shielding layers layer and are being formed along the data lines line and wider than the data lines. line, the shielding layer being formed to cover the first contact hole and the second contact hole as viewed in plan.